

Abstract

Substrate handling device for a charged particle beam system

An electron beam lithography system includes a main chamber (4) and the exchange
5 chamber (5) connected by a gate valve (7). A robot (15) is used to transfer a chuck
(8) carrying a semiconductor wafer between a cassette (10) and laser interferometer
mirror assembly (13). The robot includes a bar (17) and a side member (18)
extending laterally from the bar for supporting the chuck.

10 (Figure 2)